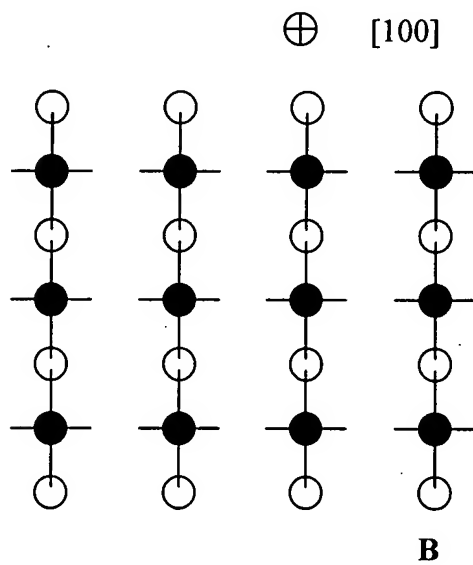
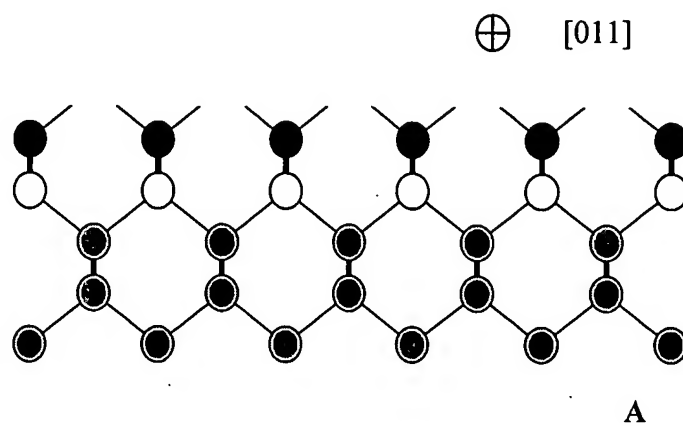


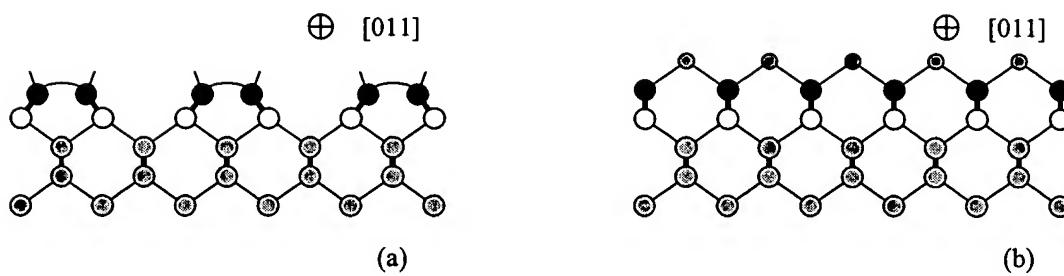
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FIGURE 1



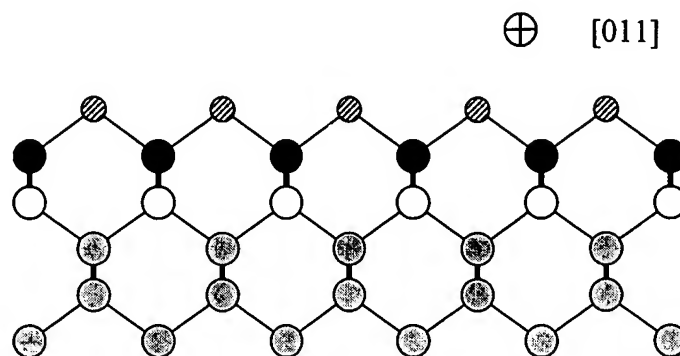
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FIGURE 2



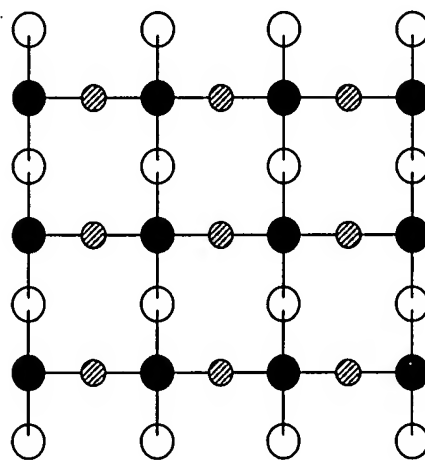
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FIGURE 3



A

\oplus [100]



B

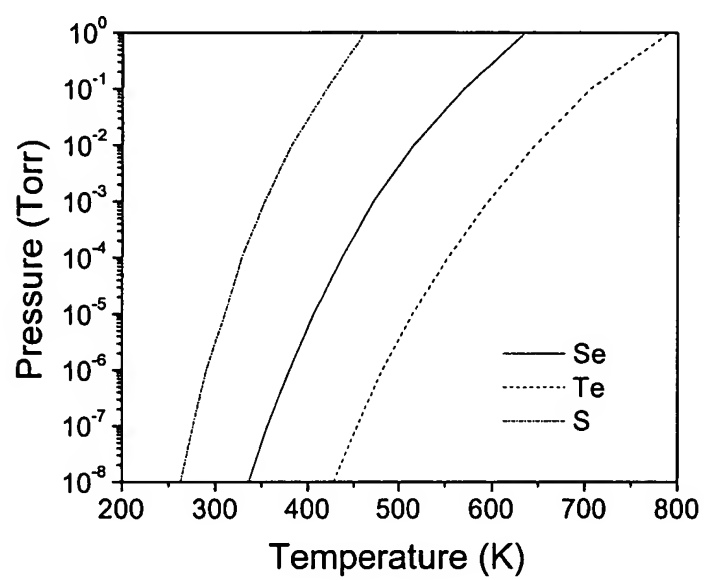
Inventor: TAO, Meng (Inventor) and WILEY, Kirk P.

Title: SUPPRESSION OF CHEMICAL REACTIVITY ON SEMICONDUCTOR SURFACES

Attorney Docket No.: 124263-1020

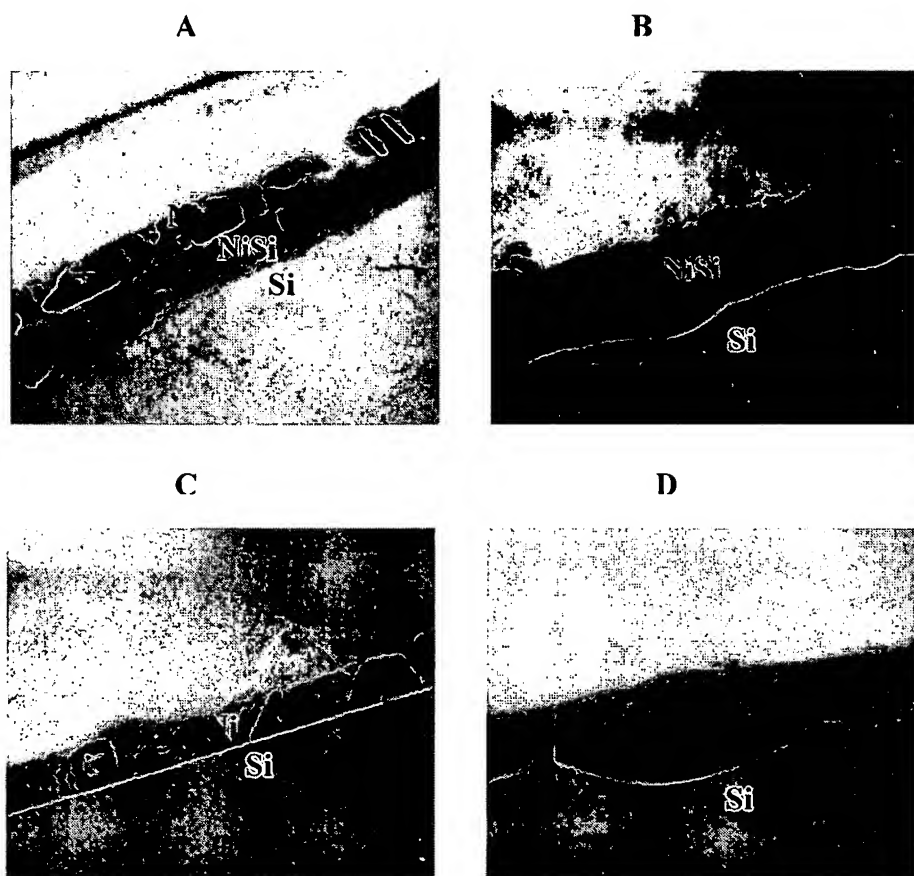
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FIGURE 4



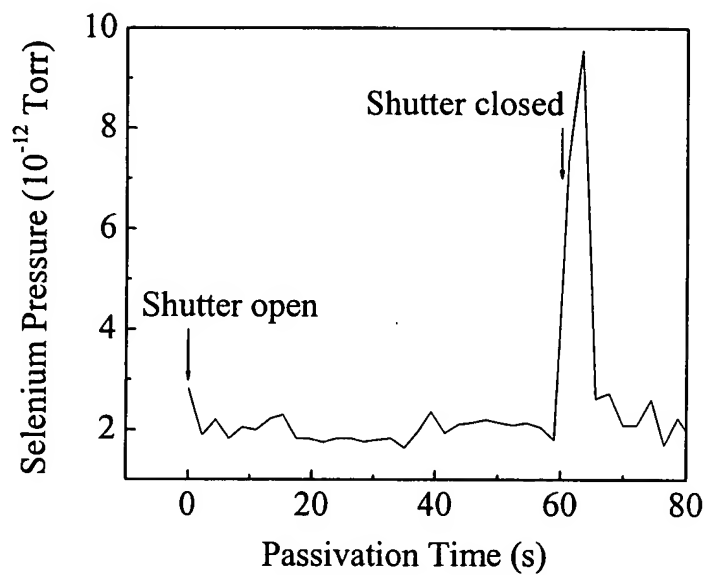
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FIGURE 5



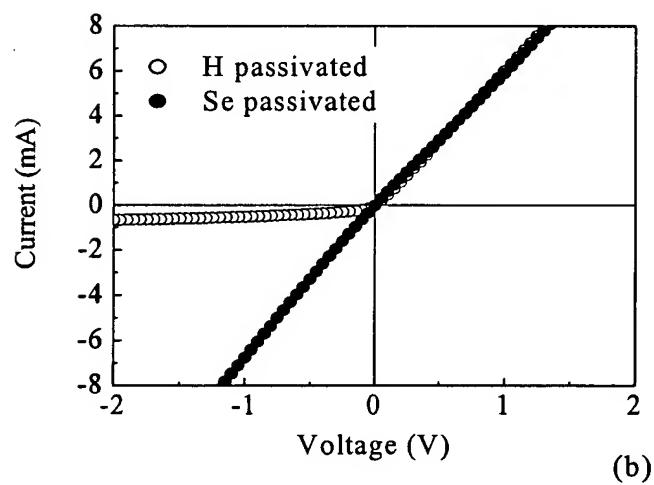
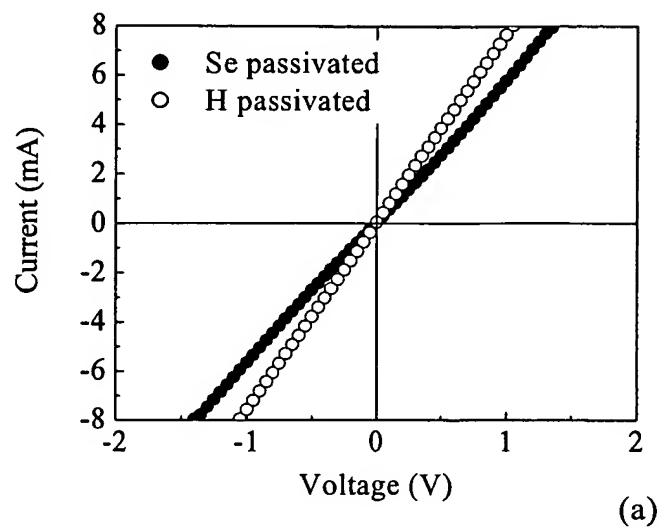
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FIGURE 6



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FIGURE 7



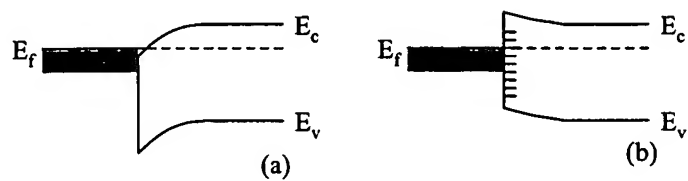
Inventor: TAO, Meng (11/11) and WILEY, Kirk P.

Title: SUPPRESSION OF CHEMICAL REACTIVITY ON SEMICONDUCTOR SURFACES

Attorney Docket No.: 124263-1020

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FIGURE 8



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FIGURE 9

